

Title (en)  
LOW DENSITY POLISHING PAD

Title (de)  
POLIERKISSEN MIT NIEDRIGER DICHT

Title (fr)  
TAMPON DE POLISSAGE À FAIBLE DENSITÉ

Publication  
**EP 3027363 A1 20160608 (EN)**

Application  
**EP 14747270 A 20140717**

Priority  
• US 201313955398 A 20130731  
• US 2014047065 W 20140717

Abstract (en)  
[origin: US2015038066A1] Low density polishing pads and methods of fabricating low density polishing pads are described. In an example, a polishing pad for polishing a substrate includes a polishing body having a density of less than 0.5 g/cc and composed of a thermoset polyurethane material. A plurality of closed cell pores is dispersed in the thermoset polyurethane material.

IPC 8 full level  
**B24B 37/24** (2012.01)

CPC (source: EP US)  
**B24B 37/205** (2013.01 - US); **B24B 37/24** (2013.01 - EP US); **B24D 11/006** (2013.01 - US); **B24D 11/04** (2013.01 - US)

Citation (search report)  
See references of WO 2015017138A1

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DOCDB simple family (publication)  
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